O' Consider a si PIN Diode with an Intrinsic Region width of W = 20 Mm. Assume that the Photon flux is 10¹⁷/cm²/sec & Absorbtion Coellicient is = 10³/cm. Then photo current density is: _____ ma/cm²?

4801:- Here Examiner Not Specified Gre => We Can't Consider Uniform generation Rate.

So, Col @ front Edge of Intrinsic region GL= = \$\phi_0 = 10^2 \colon 2/sec.

Colo @ back Edge of Intrinsic region GL= = \$\phi_0 = \frac{-\pi_w}{2} = \frac{-\pi_w}{2}

Hence, photo Current density, $J_L = 9r \% (1 - e^{-2KW}) \\
= (1.6 \times 10^{-14}) (10^{17}) (1 - exp(-10^3 (20 \times 10^{-4}))) \\
= 13.8 \text{ mA/cm}^2.$

Particular point is $I_{\nu}(x) = 0.05 \text{W/cm}^2$ at a Wave length J = 0.75 µm. Then the Greneration rate of Electron hole

Pair where Intensity is typical of Sunlight is $- \times 10^2 \text{ cm}^3 \text{ s}^{-1}$?

(cet Absolution coefficient for Grands, $K = 0.9 \times 10^4 \text{ /cm}$).

$$\frac{450i^{-1}}{h\nu} As \quad G_{L} = \frac{4 I_{\nu}(x)}{h\nu}, \quad \text{where} \quad E = h\nu = \frac{1.24}{0.75} = 1.65eV.$$

$$= 5 G_{L} = \frac{0.9 \times 10^{4} \times 0.05}{1.6 \times 10^{-19} \times 1.65} = 1.70 \times 10^{21} \text{cm}^{-3} \text{s}^{-1}.$$

(a) Coysider a Silicon premicoyductor @ T=300°K in which $N_A = 10^{16}/cm^3$ & $N_D = 3 \times 10^{15}/cm^3$. Caliculate Theoryal Equilibrium

Coycentration of Masjority Carriers — × $10^{15}/cm^3$.

Boi: Since both NA fND Exist = Compensated Semicondults.

Since NA > ND => P-type.

$$P_{0} = \frac{N_{A} - N_{0}}{2} + \sqrt{\frac{N_{A} - N_{0}}{2} + n_{i}^{2}}$$

$$P_{0} = \frac{10^{16} - 3 \times 10^{15}}{2} + \sqrt{\frac{10^{16} - 3 \times 10^{15}}{2} + (1.5 \times 10^{10})^{2}} = 7 \times 10^{15} / \text{cm}^{3}$$

(a) In a BIT of npn Transista, Emitter is doped with Phosporous of No=1016/cm3. 97 Device Maintained @ 300% Determine the Fraction of total Electrone Still in the Donas 45 tale @T=300 kg (Consider Nc = 2.8×1019/cm3) a). 41.1. b). 0.417. c). 387. d). 0.38%.

 $\frac{\sqrt{Sin_{10}}}{\sqrt{n_{0}+n_{d}}} = \frac{\sqrt{1 + \frac{N_{c}}{2N_{0}}} \exp\left(\frac{E_{0}-E_{c}}{KT}\right)}{1 + \frac{2.8 \times 10^{19}}{2 \times 10^{16}} \exp\left(\frac{-0.045}{0.026}\right)} = 0.0041 = 0.41\%$

(a). A Mosfet @ 300°k Contains an Acceptor Impurity NA = 1016/cm3. Determine the Concentration of Donas Impurity atoms that Must be added (-x10/3) for Specific Application so Hyat the sition is n-type of Fermi level is 0.20eV below Conduction boud Edge? Soi: For n-type (Non Compensated) As we KNOW, Ec-EF = KT109 No/ [for no = No).

Now for n-type Compensated, $E_{c}-E_{f}=kT\log\left|\frac{N_{c}}{N_{b}-N_{A}}\right| \Rightarrow N_{o}-N_{A}=N_{c}enp\left(\frac{E_{f}-E_{c}}{kT}\right)$

$$N_0 = 2.24 \times 10^{16} / \text{cm}^3$$
.

[: we know,

No for si@300k

is 2.8×1019/cm3].